

INFORMATION DISCLOSURE STATEMENT BY APPLICANT(S)

(Use as many sheets as necessary)

Sheet 1 of 3

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COMPLETE IF KNOWN					
Application Number	10/533,822				
Filing Date	August 31, 2005				
First Named Inventor	Mino Green				
Art Unit	2815	-			
Examiner Name	Jami M. Valentine				
Attorney Docket No.	KSTR 2 00004				

	U.S. PATENT DOCUMENTS						
Examiner Cite Initials* No.		Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document				

	FOREIGN PATENT DOCUMENTS						
Examiner	Cite	Foreign Patent Document	Publication Date	Name of Patentee or		Т	
Initials*	No.	Country Code-Number Kind Code (if known)	MM-DD-YYYY	Applicant of Cited Document			
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	AD		L					
		OTHER NON PATENT LITERATURE DOCUMENTS						
Examiner Initials* Cite No. Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published								
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	AD	J.P. Maranchi et al, Interfacial properties of the", J. Electrochem. Soc. 153(6) A1246, 2006	Γ					
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	AH	W. Lang. Silicon Micromachining Technology. Materials Science and Engineering R17 (1996) 1-55						
-	Al	T. Qiu et al, From Si nanotubes to nanowires: Synthesis, characterization, and self-assembly, Journal of Crystal Growth 277 (2005) 143–148						
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	Examiner		Date	
	Signature		Considered	

Form 1449/PTO		COMPLETE IF KNOWN						
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